

Remarks/Arguments:

The present invention relates to a method of introducing impurity wherein a reductive liquid removes the oxidized film on a solid substance and a certain desired particle is attached or introduced. The reductive liquid is at least one liquid selected from among the group consisting of hydrogen fluoride, sodium hydroxide, aqueous ammonia, sulfinic acid and adipic acid di-2-ethylhexyl ester.

Claims 1, 5, 6, 10-13, 14, 16, 17, 34, 38, 39, 43-47, 49 and 50 have been rejected under 35 U.S.C. §103(a) as being unpatentable over Mizuno, U.S. 5,851,906 in view of Suzuki, JP 08031779. Mizuno fails to teach a means for dipping the surface of the solid substance in a reductive liquid. Suzuki teaches a method for cleaning or polishing the surface of a wafer by applying a rubbing action on the surface with a liquid containing sodium hydroxide for the benefit of having a smooth surface free of any oxide residues.

Applicants have cancelled sodium hydroxide from the list of reductive liquids in the claim language. Therefore, applicants respectfully submit that the rejection has been overcome.

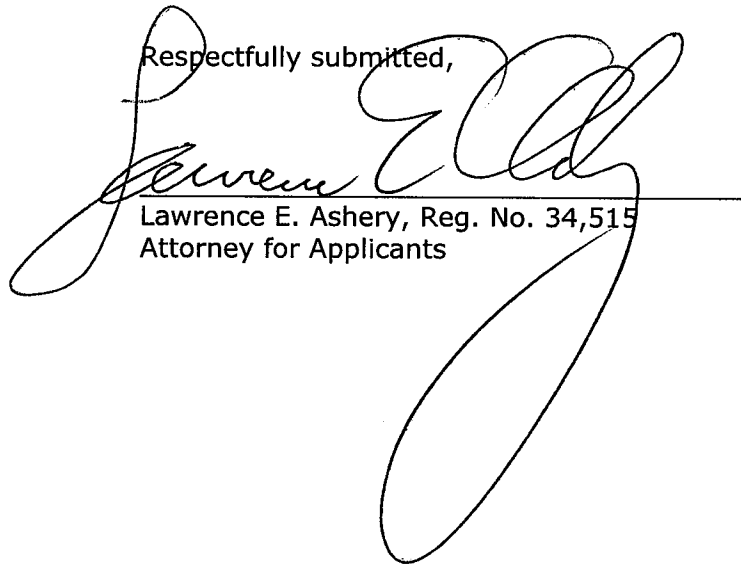
Claims 7-9, 40-42 and 48 have been rejected under 35 U.S.C. §103(a) as being unpatentable over the same references recited above. However, in light of the dependency of these claims upon the newly amended claims, applicants submit that this rejection has been overcome as well.

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In view of the amendments and the remarks set forth above, applicants submit that the above-identified application is in condition for allowance which action is respectfully requested.

Respectfully submitted,



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